

Subst. Form PTO-1449

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

(Use several sheets if necessary)

Docket Number (Optional)

SAM-0564

Application Number

Not yet assigned

Applicant

Jae-Yoon Yoo, *et al.*

Filing Date

Herewith

Group Art Unit

Not yet assigned

U. S. Patent Documents

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
	AL							
	AM							
	AN							
	AO							
	AP							
	AQ							

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

WLL	AR	Tavel, B., <i>et al.</i> , "Totally Silicided (CoSi ₂) Polysilicon: a novel approach to very low-resistive gate (~2Ω/□) without metal CMP nor etching." <i>IEDM 2001</i> , p. 825-828, December 2001
	AS	
	AT	

EXAMINER

WLL

DATE CONSIDERED

5/13/2005

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy with next communication to applicant.